IN THE CLAIMS

Please amend the claims to read as indicated below.

1 – 26. (canceled)

27. (previously presented) An illumination system, comprising:
a plate having a plurality of raster elements situated thereon for directing a light beam having a wavelength ≤ 193 nm; and
a movable carrier upon which said plate is arranged, for positioning said plate relative to said light beam.

28. (previously presented) The illumination system of claim 27, further comprising:
a reticle plane, wherein said reticle plane is defined by a y-direction and an x-direction, and
wherein said carrier is moveable in said x-direction.

29. (previously presented) The illumination system of claim 27, further comprising:
a reticle plane within which a reticle is moveable in a first direction,
wherein said carrier is moveable in a second direction.

30. (previously presented) The illumination system of claim 29, wherein said second direction is substantially perpendicular to said first direction.

31. (previously presented) The illumination system of claim 27,
wherein said light beam impinges onto said plurality of raster elements, and said plurality of raster elements partition said light beam into a plurality of light bundles, and
wherein said plurality of light bundles substantially overlap one another in a reticle plane.

32. (previously presented) The illumination system of claim 27, wherein said plate is one of a plurality of plates arranged on said carrier.

33. (canceled)

34. (previously presented) The illumination system of claim 27, wherein at least one of said plurality of raster elements comprises an actuator for positioning said at least one of said plurality of raster elements relative to said light beam.

35. (previously presented) The illumination system of claim 34, wherein said actuator changes an orientation of said raster element relative to said plate.

36. (canceled)

37. (previously presented) A system for illuminating a reticle in a reticle plane, comprising:

a plate having a plurality of raster elements situated thereon for directing a light beam having a wavelength $\leq$ 193 nm, and

a table upon which said plate is situated, for moving said plate relative to said light beam,

wherein said plurality of raster elements partition said light beam into a plurality of light bundles, and

wherein said plurality of light bundles substantially overlap one another in said reticle plane and define a ring field of illumination in said reticle plane.

38. (previously presented) The illumination system of claim 37,

wherein said plurality of light bundles substantially overlap one another in a reticle plane of said illumination system and define a ring field of illumination in said reticle plane, and

wherein at least one of said plurality of raster elements is adjustable to change said ring field of illumination in said reticle plane.

39. (previously presented) The illumination system of claim 38, wherein said at least one of said plurality of raster elements, when adjusted to change said ring field of illumination in said reticle plane, also changes an illumination in an exit pupil of said illumination system.

40. (previously presented) The system of claim 38, wherein said at least one of said plurality of raster elements is tiltable.

41. (previously presented) The system of claim 38, wherein said at least one of said plurality of raster elements is displaceable.

42. (previously presented) The system of claim 38, wherein said at least one of said plurality of raster elements is replaceable.

43 – 46. (canceled)

47. (currently amended) A projection exposure apparatus, comprising:

(a) an illumination system for illuminating an object with light having a wavelength ≤ 193 nm,

wherein said illumination system includes (i) a plate having ~~a~~ a plurality of raster elements situated thereon, and (ii) a movable carrier upon which said plate is arranged, for positioning said plate relative to a beam of said light; and

(b) a projection objective for imaging said object onto a light sensitive substrate.

48. (previously presented) The projection exposure apparatus of claim 47, wherein said object is a pattern-bearing mask.

49. (currently amended) A method for manufacturing a microelectronic component, comprising using an projection exposure having:

(a) an illumination system for illuminating an object with light having a wavelength ≤ 193 nm,

wherein said illumination system includes (i) a plate having ~~a a~~ plurality of raster elements situated thereon, and (ii) a movable carrier upon which said plate is arranged, for positioning said plate relative to a beam of said light; and

(b) a projection objective for imaging said object onto a light sensitive substrate.

50. (new) The illumination system of claim 27,

wherein said plurality of raster elements is a first plurality of raster elements, and

wherein said illumination system further comprises:

a second plurality of raster elements that receives said light beam from said first plurality of raster elements.

51. (new) The illumination system of claim 27, wherein said plurality of raster elements is a plurality of reflective raster elements.

52. (new) The system of claim 37, wherein said plurality of raster elements is a plurality of reflective raster elements.

53. (new) The projection exposure apparatus of claim 47, wherein said plurality of raster elements is a plurality of reflective raster elements.

54. (new) The method of claim 49, wherein said plurality of raster elements is a plurality of reflective raster elements.

55. (new) An illumination system, comprising:

a first plate having a first plurality of raster elements situated thereon for directing a light beam having a wavelength ≤ 193 nm;

a movable carrier upon which said first plate is arranged, for positioning said plate relative to said light beam, and;

a second plate having a second plurality of raster elements that receives said light beam from said first plurality of raster elements, wherein said second plate is in a fixed position.

56. (new) The illumination system of claim 55,

wherein said first plurality of raster elements produces a plurality of images of a source of said light, and

wherein said second plurality of raster elements is situated at or near said plurality of images.